

REMARKS

Claims 1 and 8 are amended herein to incorporate the subject matter of claims 4 and 12, respectively. Claims 4 and 12 are canceled. Hence no new matter is presented.

Entry of the Amendment after Final rejection is deemed proper and is respectfully requested since the amendment to independent claims 1 and 8 merely incorporates subject matter of dependent claims 4 and 12, and therefore does not raise new issues for further search.

Accordingly, upon entry of the Amendment, claims 1-3, 5 and 8-11 will be all of the claims pending in the application.

Claims 1-5 and 8-12 are rejected under 35 U.S.C. § 103 as allegedly being unpatentable over Li et al.

Applicants respectfully traverse the rejection and submit that Li et al does not teach or suggest the presently claimed invention as recited in amended claims 1 and 8.

Independent claims 1 and 8, as amended, recite that step (b) is carried out 1 to 10 seconds after step (a) is carried out. It is disclosed in the specification at page 12, lines 8-19, that a large amount of a first gas is supplied from gas nozzle 22 into the chamber with a delay of 1 to 10 seconds after the supply of a small amount of gas from gas nozzle 21, which supplies a second gas at a second smaller flow rate. It is further disclosed that when the delay is less than 1 second, a film starts to form from an outer peripheral portion of the wafer, as in conventional techniques. Also when the delay is equal to or larger than 10 seconds, the film quality of an initial oxide film formed before the SiH₄ gas is introduced from the gas nozzle 22

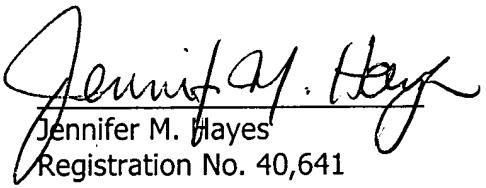
deteriorates, and the insulation breakdown of the oxide film occurs. Therefore this condition is not suitable.

Li et al does not teach or suggest the element of the delay between step (a) and (b) as recited in independent claims 1 and 8, as amended. Further, Li et al does not even recognize the beneficial effect of the delay between steps (a) and (b). Thus, Li et al does not render the presently claimed invention obvious.

In view of the above, reconsideration and allowance of this application are now believed to be in order, and such actions are hereby solicited. If any points remain in issue which the Examiner feels may be best resolved through a personal or telephone interview, the Examiner is kindly requested to contact the undersigned at the telephone number listed below.

The USPTO is directed and authorized to charge all required fees, except for the Issue Fee and the Publication Fee, to Deposit Account No. 19-4880. Please also credit any overpayments to said Deposit Account.

Respectfully submitted,



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Date: May 18, 2005